WHAT IS CLAIMED IS:

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- 1. A semiconductor optical device comprising:
- a semiconductor substrate having a main surface;
- a stripe-shaped optical waveguide, disposed on said main surface of said semiconductor substrate, including an active layer;
- a current blocking part, disposed on said semiconductor substrate, having said optical waveguide buried therein;
- a electrically conductive layer disposed on said optical waveguide and current blocking part;
 - a first electrode electrically connected to said semiconductor substrate, and a second electrode electrically connected to said electrically conductive layer; and
 - a trench having a bottom in contact with said current blocking part.
 - 2. A semiconductor optical device according to claim 1, wherein said current blocking part includes a blocking semiconductor layer comprising an InP semiconductor doped with Fe.
 - 3. A semiconductor optical device according to claim 2, wherein said blocking semiconductor layer has a thickness of at least 1 μm .
- 4. A semiconductor optical device according to claim 2, wherein said current blocking part further includes

a hole blocking layer comprising an InP semiconductor of a conductivity type opposite from that of said electrically conductive layer.

5. A semiconductor optical device according to claim 2, wherein said blocking semiconductor layer has an Fe concentration of at least $5 \times 10^{15} \text{ cm}^{-3}$.

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- 6. A semiconductor optical device according to claim 2, wherein said blocking semiconductor layer has an Fe concentration of 5 \times 10¹⁶ cm⁻³ or less.
- 7. A semiconductor optical device according to claim 1, further comprising an insulating film disposed on a surface of said trench.
- 8. A semiconductor optical device according to claim 7, wherein said insulating film comprises an insulating silicon compound.
- 9. A semiconductor optical device according to claim 1, wherein said optical waveguide comprises a first conductivity type semiconductor layer, a second conductivity type semiconductor layer, and an active layer;

said active layer being provided between said first and second conductivity type semiconductor layers.

- 10. A semiconductor laser device comprising the semiconductor optical device according to claim 9.
- 11. A semiconductor optical modulation device comprising the semiconductor optical device according to claim 9.

12. A semiconductor optical integrated device comprising:

a semiconductor substrate having a main surface, said main surface including a laser device region and an optical modulation device region arranged in a predetermined direction;

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- a stripe-shaped first optical waveguide longitudinally extending in said predetermined direction on said laser device region;
- a stripe-shaped second optical waveguide longitudinally extending in said predetermined direction on said optical modulation device region;
 - a current blocking part, disposed on said semiconductor substrate, having both of said first and second optical waveguides buried therein;
 - a electrically conductive layer disposed on said current blocking part and first optical waveguide on said laser device region;
 - a electrically conductive layer disposed on said current blocking part and second optical waveguide on said optical modulation device region;
 - a first electrode electrically connected to said semiconductor substrate, a second electrode electrically connected to said electrically conductive layer on said laser device region, and a third electrode electrically connected to said electrically conductive layer on said optical

modulation device region; and

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a trench extending in said predetermined direction along said first and second optical waveguides and having a bottom in contact with said current blocking part;

each of said first and second optical waveguides including a first conductivity type semiconductor layer, a second conductivity type semiconductor layer, and an active layer;

said active layer being provided between said first and second conductivity type semiconductor layers.